

REMARKS

Claims 1-24 are pending in the application. Claims 1-6, 13-21, and 23 stand rejected. Claims 7-12, 22, and 24 are objected to. By the present amendment, the specification and claims 1, 4, 6, 7-13, 21-24 have been amended. The Examiner's reconsideration of the claim rejections in view of the above amendments and following remarks is respectfully requested.

In the Specification:

The specification has been amended to coincide with the claims and figures contain therein. Corrections to the figures embedded in the text are indicated in red ink.

Allowable Subject Matter:

Applicants gratefully acknowledge Examiner's indication that claims 7-12, 22, and 24 would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

Applicants respectfully submit that the claims 7 and 22 have been amended essentially as recommended by the Examiner. Claims 8-12 depend from claim 7. Claim 24 depends from claim 22. Accordingly, claims 8-12 and 22 are believed to be allowable because they depend from allowable base claims 7 and 22, respectively. Withdrawal of the claim objections is respectfully requested.

Claim Objections:

Claims 21 and 22 are objected for the reasons as set forth on page 2 of the Office Action dated March 26, 2003.

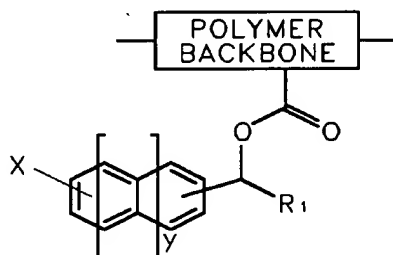
Applicants respectfully submit that claims 21 and 22 have been amended essentially as recommended by the Examiner. Accordingly, withdrawal of the claim objections is respectfully

requested.

Claim Rejections- 35 U.S.C. § 102(e):

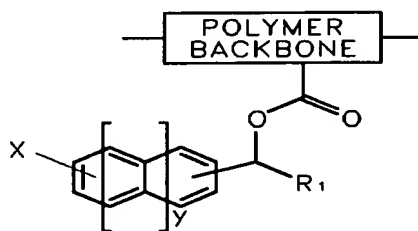
Claims 1-4 are rejected under 35 U.S.C. 102(e) as being anticipated by Stolka et al. (U.S. 4,117,239). Claims 1-6 are rejected under 35 U.S.C. 102(e) as being anticipated by Pavelchek (U.S. 2002/0195419 A1). Claims 1-6, 13-17, 21, and 23 are rejected under 35 U.S.C. 102(e) as being anticipated Pavelchek et al. (U.S. 6,316,165).

Claim 1 recites, *inter alia*, *A photosensitive polymer having an acid-labile protecting group represented by the formula:*



wherein the acid-labile protecting group comprises a fused aromatic ring; R₁ is alkyl group having from 2 to 4 carbon atoms; X is halogen, alkyl, or alkoxy; and y is an integer from 1 to 3.

Claim 13 recites, *inter alia*, *A photosensitive composition comprising (a) A photosensitive polymer having an acid-labile protecting group represented by the formula:*



wherein the acid-labile protecting group comprises a fused aromatic ring; R_1 is an alkyl group having from 1 to 4 carbon atoms; X is a halogen, alkyl, or alkoxy, and y is an integer from 1 to 3; and (b) a photoacid generator (PAG).

With respect to claim 1, Applicants respectfully submit that there is nothing in Stolka, Pavelchek or Pavelchek et al. that discloses a photosensitive polymer comprising, *inter alia*, an acid-labile protecting group comprising a fused aromatic ring, as shown above, where R_1 is alkyl group having from 2 to 4 carbon atoms; X is a halogen, alkyl, or alkoxy; and y is an integer from 1 to 3. Thus, Applicants respectfully submit that the photosensitive polymer with the acid-labile protecting comprising a fused aromatic ring and the functional groups listed above as claimed in claim 1 of the present invention is patentably distinct and not anticipated either Stolka, Pavelchek or Pavelchek et al.

Further, with respect to claim 13, Applicants respectfully submit that claim 13 is allowable for at least the same reasons as stated above for claim 1. Namely, there is nothing in Pavelchek et al. that discloses a photoresist composition comprising (a) a photosensitive polymer having an acid-labile protecting group, as shown above in claim 13, wherein the acid-labile protecting group comprises a fused aromatic ring; R_1 is an alkyl group having from 1 to 4 carbon atoms; X is a halogen, alkyl, or alkoxy, and y is an integer from 1 to 3, as essentially claimed in claim 13. Thus, Applicants respectfully submit that the photosensitive composition with a photosensitive polymer having an acid-labile protecting group including a fused aromatic ring and the functional groups listed above as claimed in claim 13 of the present invention is patentably distinct and not anticipated by Pavelchek et al.

Since claims 2-6 depend, directly and indirectly, from claim 1 and claims 14-21 and 23

depend, directly and indirectly, from claim 13, claims 2-6 and claims 14-21 and 23 are believed to be patentably distinct and patentable over the cited references for at least the same reasons given above for claims 1 and 13, respectively. Accordingly, withdrawal of the claim rejections under 35 U.S.C. § 102 is respectfully requested.

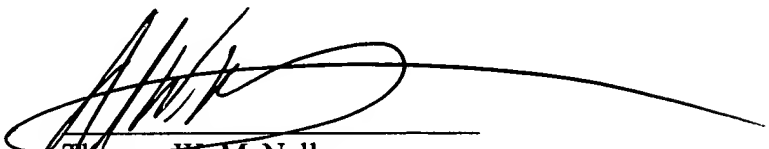
Claim Rejections- 35 U.S.C. § 103(a):

Claims 18-20 are rejected under 35 U.S.C. § 103(a) as being unpatentable over Pavelchek (U.S. 6,316,165) as applied to claims 1-6, 13-17, 21, and 23 above and in further view of Choi (U.S. 6,045,970).

The remaining claims 18-20 are dependent upon independent base claim 1, which is believed to be allowable for the reasons stated above, and therefore, Applicants respectfully submit that the above rejection is believed to be moot with respect to these dependent claims.

In view of the foregoing amendments and remarks, it is respectfully submitted that all the claims now pending in the application are in condition for allowance. Early and favorable action is respectfully requested.

Respectfully submitted,

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